

Joseph P, Klesko

List of Publications by Citations

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12

papers

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ext. papers

223

ext. citations

7.7

avg, IF

3.2

L-index

#	Paper	IF	Citations
12	Low Temperature Thermal Atomic Layer Deposition of Cobalt Metal Films. <i>Chemistry of Materials</i> , 2016 , 28, 700-703	9.6	48
11	Low Temperature, Selective Atomic Layer Deposition of Cobalt Metal Films Using Bis(1,4-di-tert-butyl-1,3-diazadienyl)cobalt and Alkylamine Precursors. <i>Chemistry of Materials</i> , 2017 , 29, 7458-7466	9.6	34
10	Substrate selectivity in the low temperature atomic layer deposition of cobalt metal films from bis(1,4-di-tert-butyl-1,3-diazadienyl)cobalt and formic acid. <i>Journal of Chemical Physics</i> , 2017 , 146, 052813 ³⁹	9.6	29
9	Low Temperature, Selective Atomic Layer Deposition of Nickel Metal Thin Films. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 14200-14208	9.5	21
8	Thermal Atomic Layer Deposition of Titanium Films Using Titanium Tetrachloride and 2-Methyl-1,4-bis(trimethylsilyl)-2,5-cyclohexadiene or 1,4-Bis(trimethylsilyl)-1,4-dihydropyrazine. <i>Chemistry of Materials</i> , 2015 , 27, 4918-4921	9.6	20
7	Selective Atomic Layer Deposition Mechanism for Titanium Dioxide Films with (EtCp)Ti(NMe ₂) ₃ : Ozone versus Water. <i>Chemistry of Materials</i> , 2018 , 30, 970-981	9.6	14
6	Reactivity of Atomic Layer Deposition Precursors with OH/H ₂ O-Containing Metal Organic Framework Materials. <i>Chemistry of Materials</i> , 2019 , 31, 2286-2295	9.6	11
5	Thermal Atomic Layer Etching of Silica and Alumina Thin Films Using Trimethylaluminum with Hydrogen Fluoride or Fluoroform. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 31784-31794	9.5	9
4	Unusual stoichiometry control in the atomic layer deposition of manganese borate films from manganese bis(tris(pyrazolyl)borate) and ozone. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 051515	2.9	2
3	Mechanistic study of the atomic layer deposition of scandium oxide films using Sc(MeCp) ₂ (Me ₂ pz) and ozone. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 011504	2.9	2
2	Selective Growth of Interface Layers from Reactions of Sc(MeCp)(Mepz) with Oxide Substrates. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 32818-32827	9.5	2
1	Metallic Materials Deposition: Metal-Organic Precursors Update based on the original article by Charles H. Winter, Wenjun Zheng and Hani M. El-Kaderi, Encyclopedia of Inorganic Chemistry Second Edition, © 2005, John Wiley & Sons, Ltd. 2012 ,	1	